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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/768,092	02/02/2004	Kozo Makiyama	020212A	8674
38834	7590 10/07/2005		EXAM	INER
WESTERMAN, HATTORI, DANIELS & ADRIAN, LLP			POMPEY, RON EVERETT	
1250 CONNE SUITE 700	ECTICUT AVENUE, N	N .	ART UNIT	PAPER NUMBER
	ON, DC 20036		2812	

DATE MAILED: 10/07/2005

Please find below and/or attached an Office communication concerning this application or proceeding.

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	Application No.	Applicant(s)	
	10/768,092	MAKIYAMA ET AL.	
Office Action Summary	Examiner	Art Unit	
	Ron E. Pompey	2812	
The MAILING DATE of this communication ap Period for Reply	ppears on the cover sheet	with the correspondence address	•
A SHORTENED STATUTORY PERIOD FOR REPLY WHICHEVER IS LONGER, FROM THE MAILING IDENTED TO THE	DATE OF THIS COMMU .136(a). In no event, however, may d will apply and will expire SIX (6) Note, cause the application to become	NICATION. ra reply be timely filed IONTHS from the mailing date of this communical ABANDONED (35 U.S.C. § 133).	
Status			
 1) Responsive to communication(s) filed on 14. 2a) This action is FINAL. 2b) Th 3) Since this application is in condition for allow closed in accordance with the practice under 	is action is non-final. ance except for formal m		s is
Disposition of Claims			
4) ☐ Claim(s) 1-11 is/are pending in the applicatio 4a) Of the above claim(s) 4 and 7-11 is/are w 5) ☐ Claim(s) is/are allowed. 6) ☐ Claim(s) 1-3,5 and 6 is/are rejected. 7) ☐ Claim(s) is/are objected to. 8) ☐ Claim(s) are subject to restriction and/	ithdrawn from considerat	ion.	
Application Papers			
9) ☐ The specification is objected to by the Examir 10) ☑ The drawing(s) filed on 02 February 2004 is/a Applicant may not request that any objection to the Replacement drawing sheet(s) including the corre 11) ☐ The oath or declaration is objected to by the E	re: a)⊠ accepted or b)[e drawing(s) be held in abe ction is required if the draw	yance. See 37 CFR 1.85(a). ing(s) is objected to. See 37 CFR 1.12	
Priority under 35 U.S.C. § 119			
a) Acknowledgment is made of a claim for foreig a) All b) Some * c) None of: 1. Certified copies of the priority documents. 2. Certified copies of the priority documents. 3. Copies of the certified copies of the priority application from the International Bure. * See the attached detailed Office action for a list	nts have been received. nts have been received in ority documents have be au (PCT Rule 17.2(a)).	n Application No. <u>10/084,924</u> . en received in this National Stage	
Attachment(s) 1) Notice of References Cited (PTO-892) 2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08 Paper No(s)/Mail Date 2-2-04.	Paper	w Summary (PTO-413) No(s)/Mail Date of Informal Patent Application (PTO-152) 	

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DETAILED ACTION

Claim Rejections - 35 USC § 102

1. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.
- 2. Claims 1 and 3 are rejected under 35 U.S.C. 102(b) as being anticipated by Yoshida (US 5,712,175).

Yoshida discloses the limitations of:

- (a) preparing a semiconductor substrate having current input/output regions (2a,2b, fig. 1);
- (b) forming an insulating layer (3, fig. 2) on the semiconductor substrate (col. 4, lns. 23 28);
 - (c) forming a resist laminate (6 and 3, fig. 7) on the insulating layer;
- (d) forming an upper opening through an upper region (6a, fig. 7) of the resist laminate, the upper opening having a laterally broadening middle space;
- (e) forming a lower opening (5, fig. 5) through a lower region of the resist laminate, the lower opening communicating the upper opening, having a limited size along a current direction, and having generally vertical sidewalls;
 - (f) etching the insulating layer (3, fig. 5) exposed in the lower opening;
- (g) performing a heat treatment of the resist laminate to deform the side walls(3b, fig. 6) of the lower opening so that at least one of opposite ends of the lower region

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at the lower opening is retarded from a corresponding end of the insulating layer and that the lower opening has a forward taper shape upwardly and monotonically increasing a size of the lower opening along the current direction;

(h) filling a gate electrode stem in the lower opening and forming a head (7, fig. 8) in the upper opening, the head having an expanded size along the current direction; wherein the heat treatment in said step (g) makes the opposite side walls of the lower opening along the current direction have a generally symmetric taper shape and

be retarded from opposite ends of the insulating layer (col. 3, In. 39 – col. 4, In. 22).

Claim Rejections - 35 USC § 103

- 3. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 4. Claims 2, 5 and 6 are rejected under 35 U.S.C. 103(a) as being unpatentable over Yoshida (US 5,712,175) as applied to claims 1 and 3 above, in view of Sasaki et al. (US 6,180,528).

Yoshida reads on the claims as applied above and applying an energy beam to an upper region of said resist laminate for defining an upper opening in element regions, and applying an energy beam to a lower region of said resist laminate in at least part of said element region at a dose depending on the element region, but does not disclose the claimed limitation(s) of:

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a plurality of element regions and

wherein the heat treatment in said step (g) is performed at a temperature lower than a glass transition temperature of the lower region of the resist laminate... However,

Sasaki discloses the above claimed limitations regarding: a.

Performing a heat treatment on the lower resist at a temperature lower than a glass transition temperature in column(s) 5, line(s) 14-20.

Therefore, it would have been obvious to one of ordinary skill in the art at the time of the invention to combine Sasaki with Yoshida, because this will cure the sheet and improve precision during etching.

b. It would have been obvious to one of ordinary skill in the art at the time the invention was made to make more than one element since it has been held that mere duplication of essential working parts of a device involves only routine skill in the art. St. Regis Paper Co. v. Bemis Co., 193 USPQ 8.

Therefore, it would have been obvious to one of ordinary skill in the art at the time of the invention that more than one element could be formed simultaneously to allow faster production of devices.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Ron E. Pompey whose telephone number is (571) 272-1680. The examiner can normally be reached on compressed.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Michael S. Lebentritt can be reached on (571) 272-1873. The fax phone

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number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

October 3, 2005

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